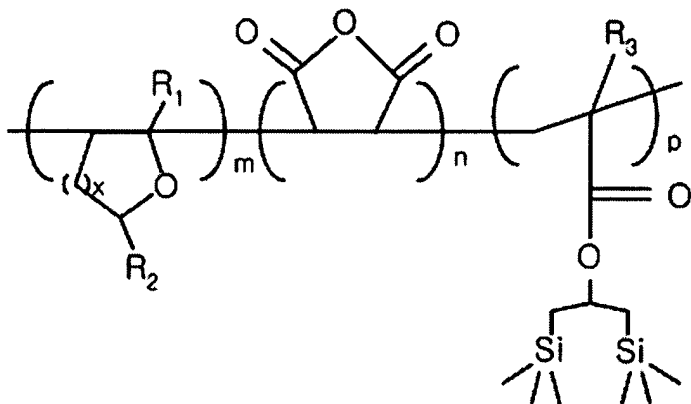


A PHOTSENSITIVE POLYMER CONTAINING SILICON AND A RESIST COMPOSITION USING THE SAME

ABSTRACT OF THE DISCLOSURE

5 A photosensitive polymer including silicon and a resist composition using the same are disclosed. The photosensitive polymer has the following formula 1.

<Formula 1>



10 In formula 1, R₁ of the first monomer and R₃ of the third monomer are an alkyl group. R₂ of the first monomer is hydrogen, alkyl, alkoxy, or carbonyl. The X of the first monomer is an integer selected from 1 to 4. Further, m/(m+n+p) is about 0.1 to about 0.4, n/(m+n+p) is about 0.1 to about 0.5, and p/(m+n+p) is about 0.1 to about 0.4.

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